

FIG. 1A

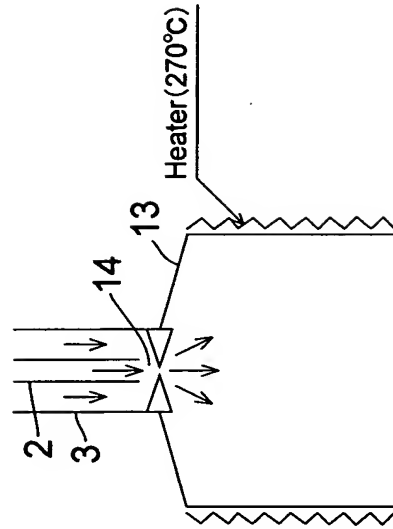


FIG. 1B

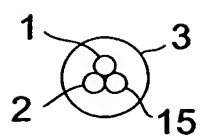


FIG. 2C

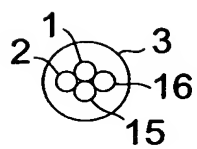


FIG. 2D

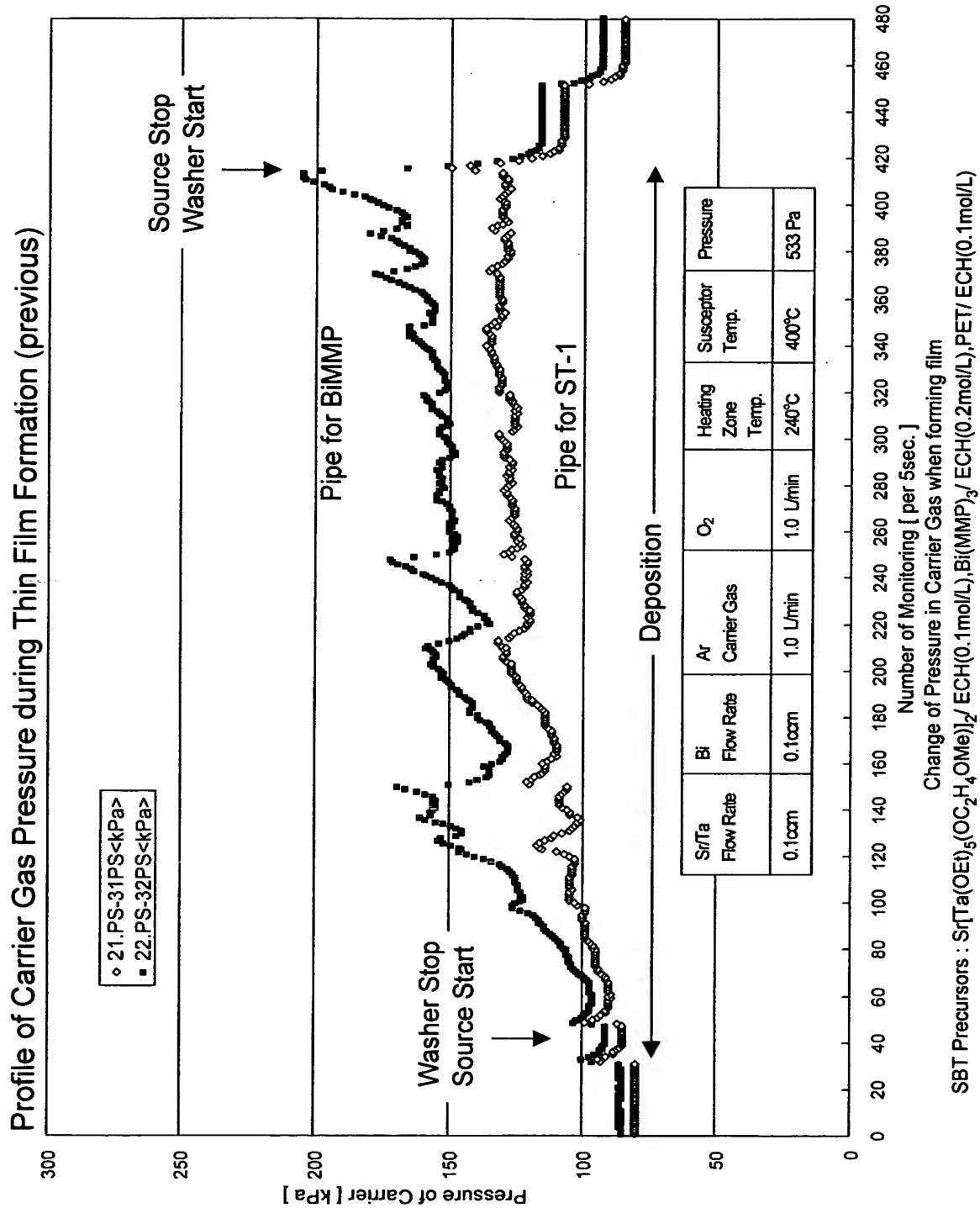


FIG.3

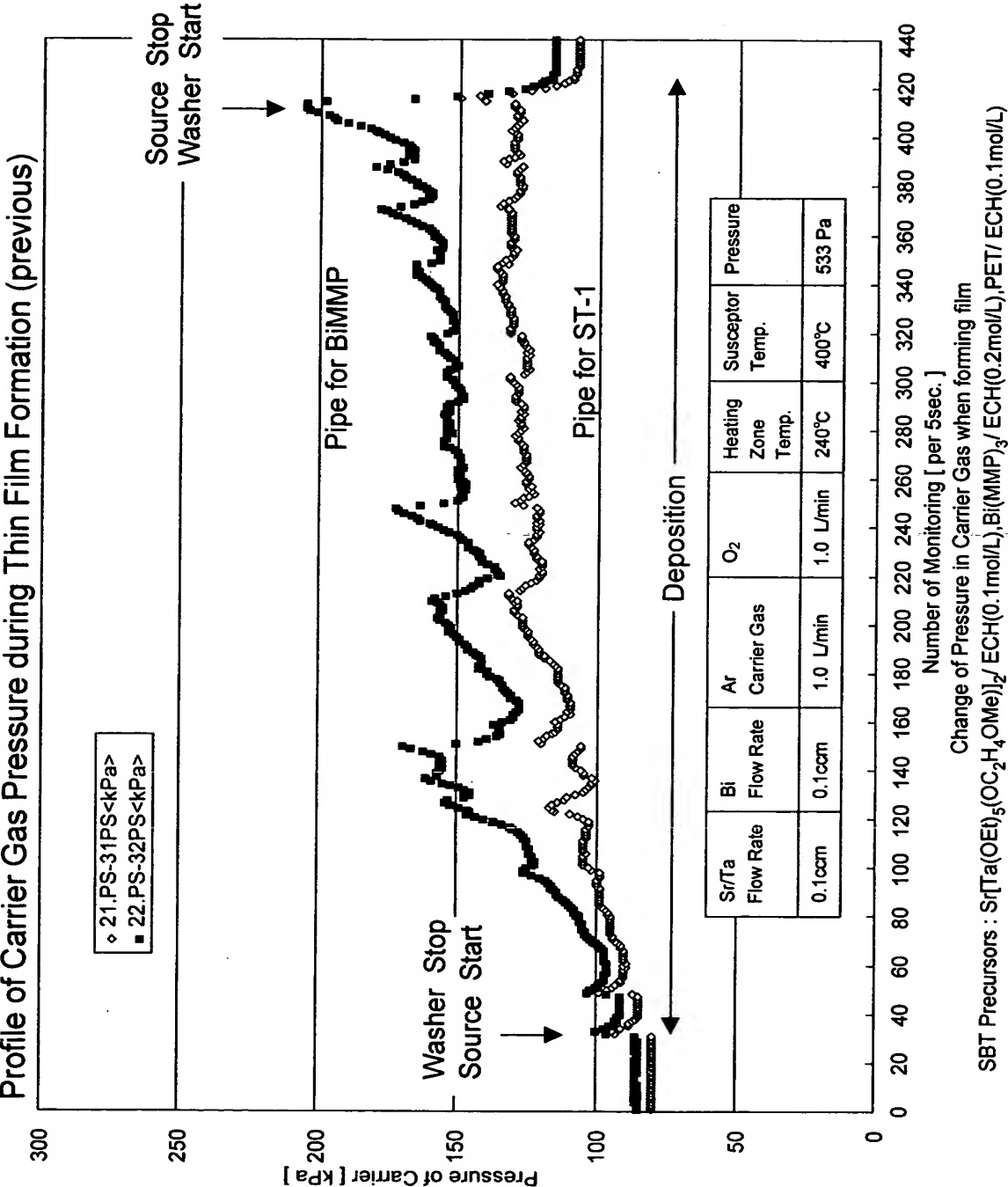


FIG.4

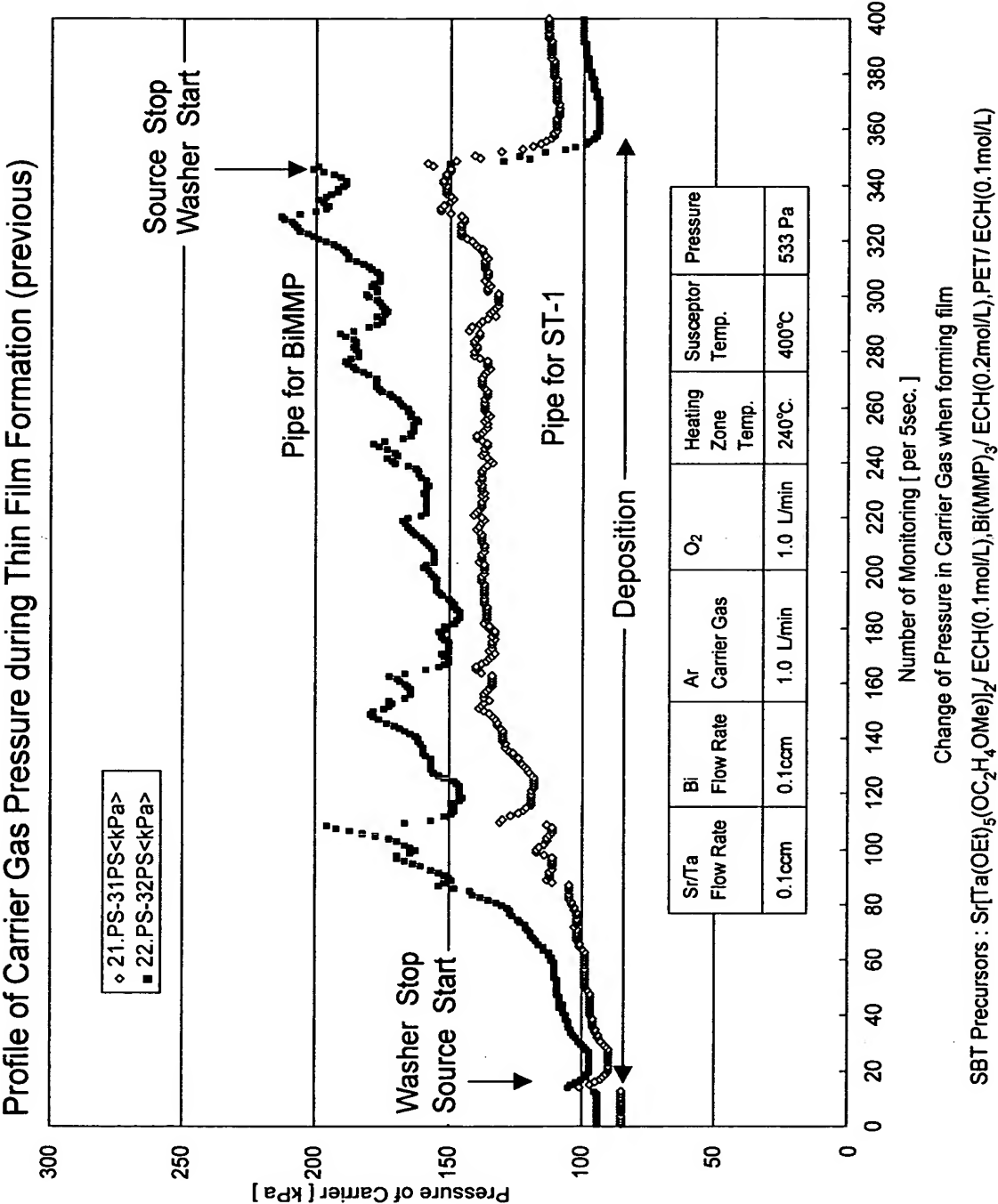


FIG.5

Profile of Carrier Gas Pressure during Thin Film Formation (previous)

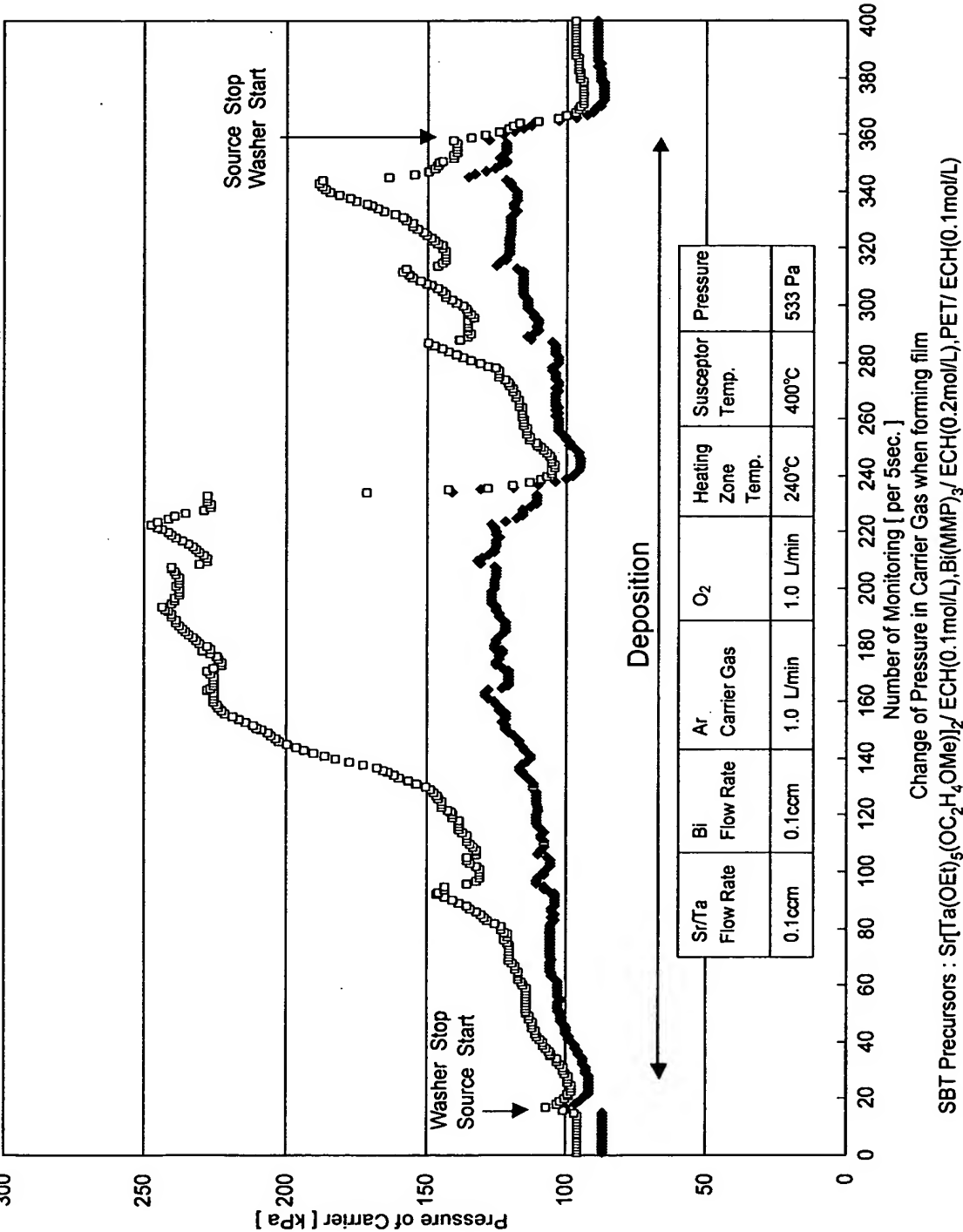


FIG.6

Profile of Carrier Gas Pressure during Thin Film Formation (previous)

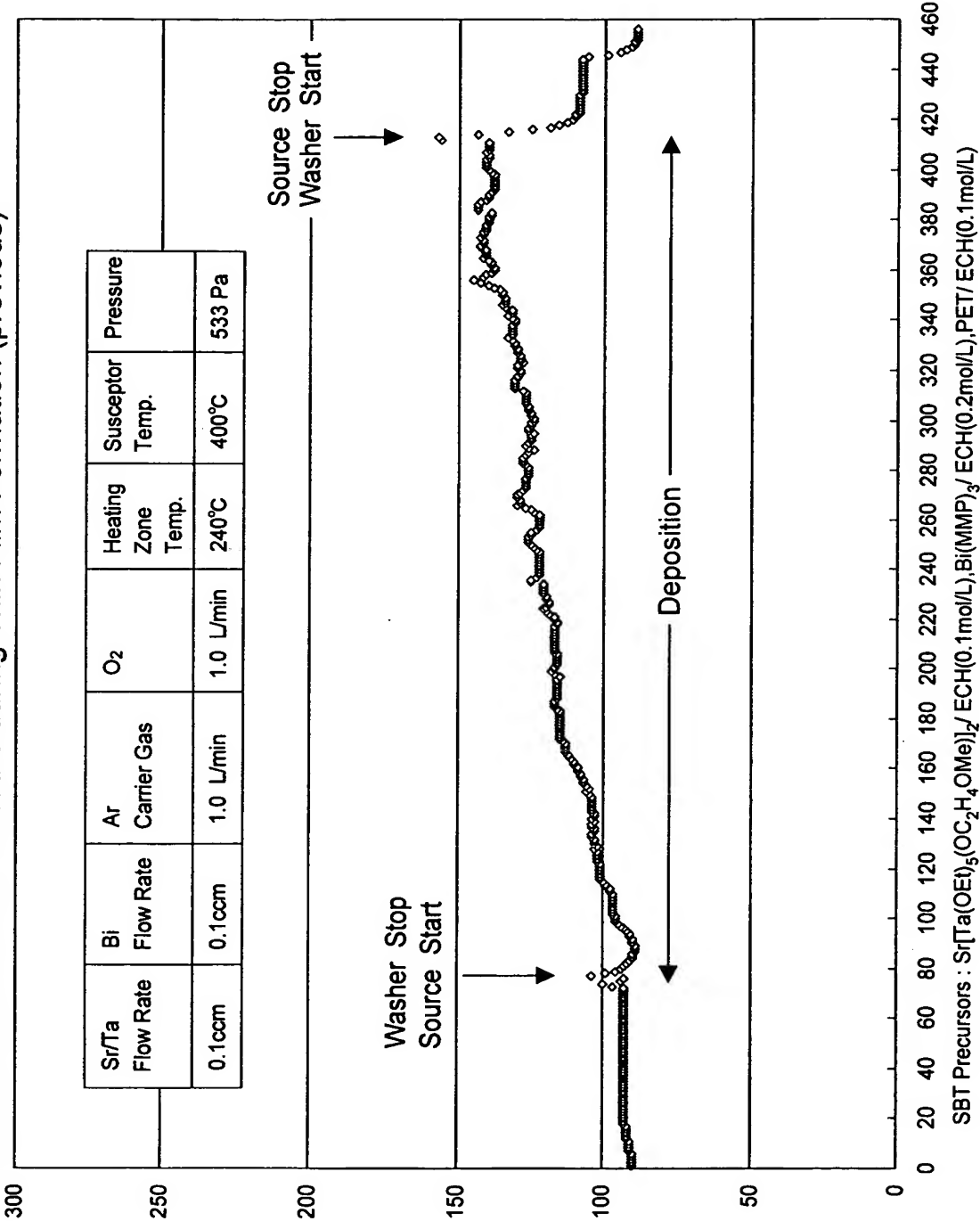
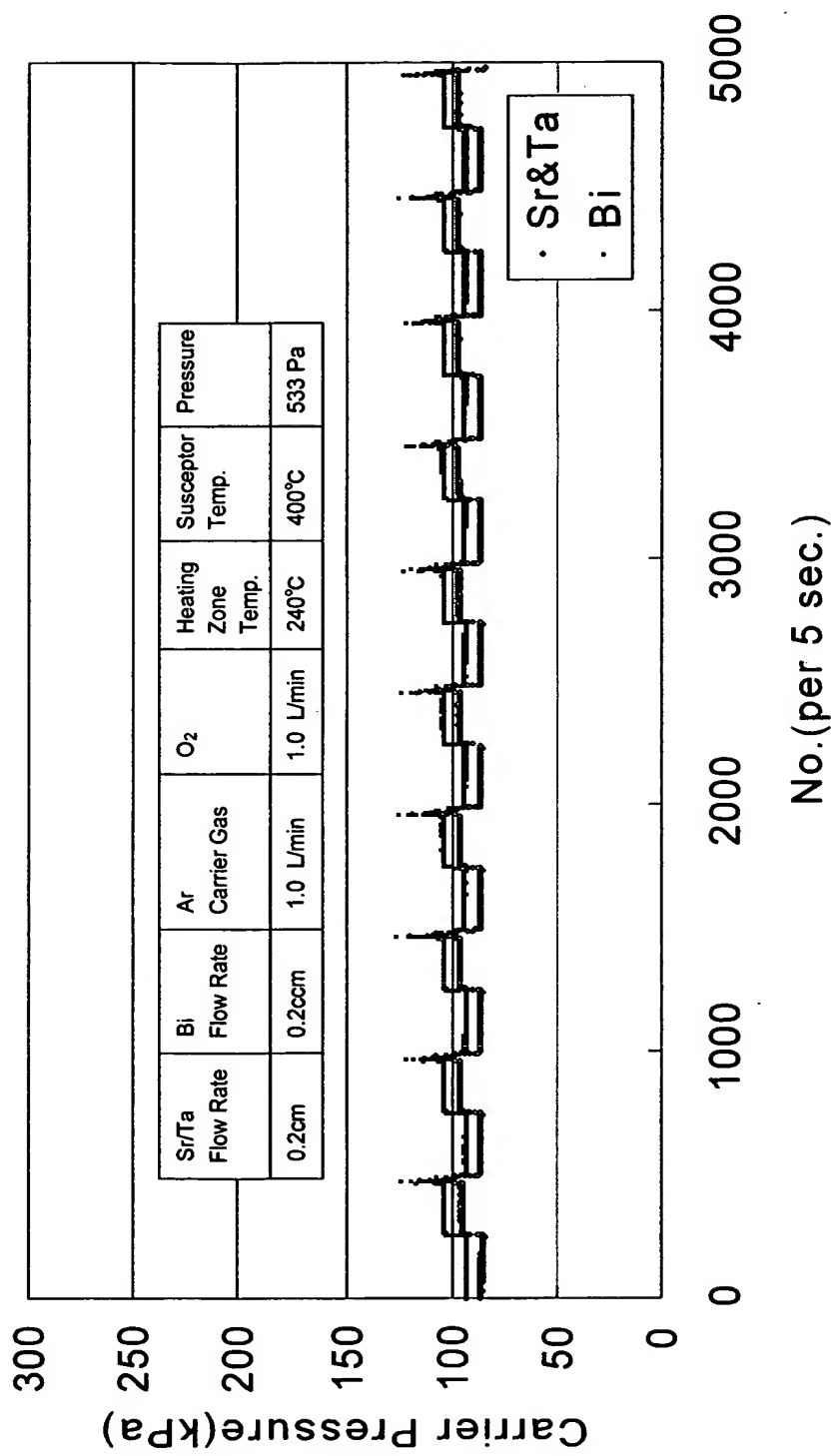


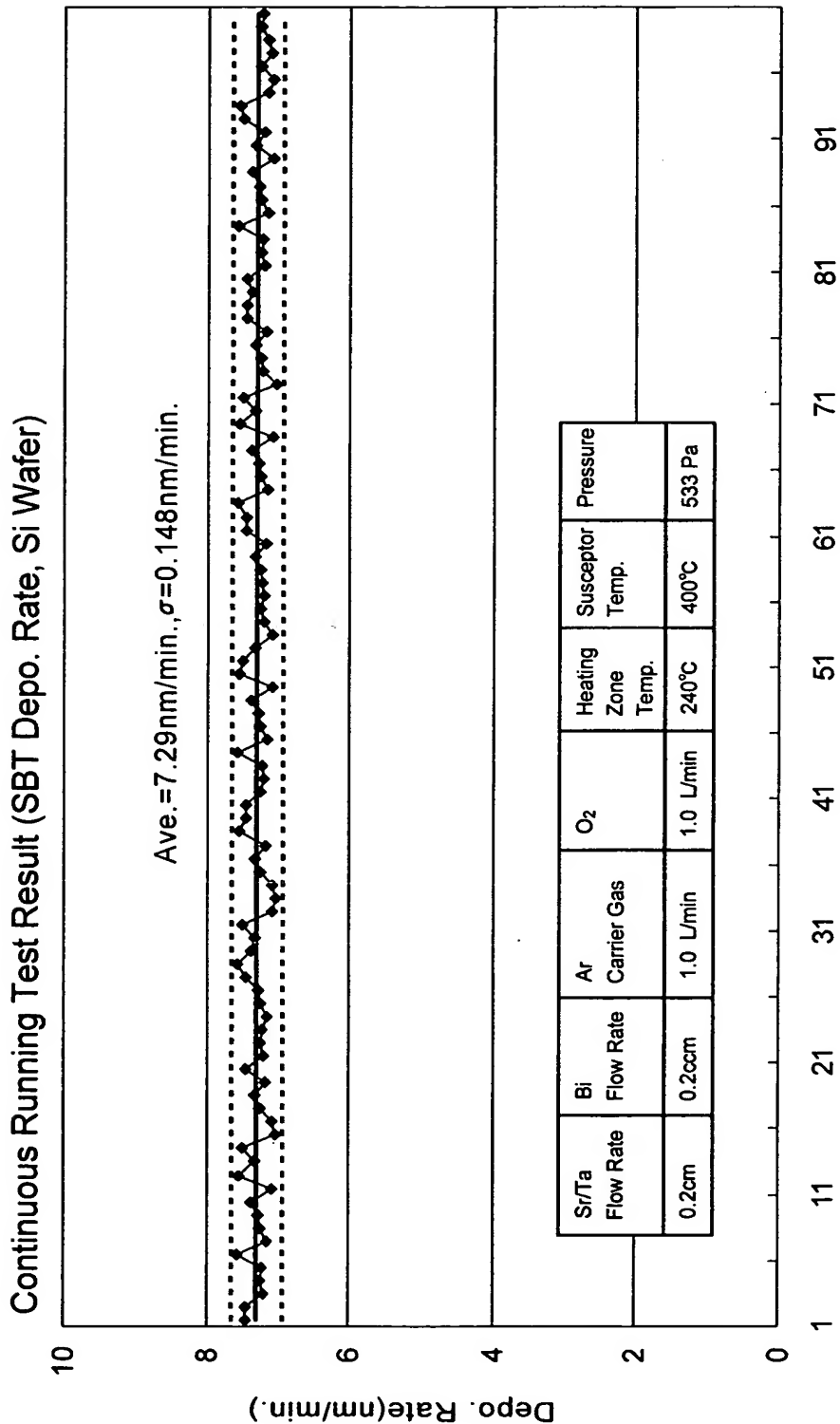
FIG.7

Profile of Carrier Gas Pressure during Thin Film Formation (Current)



SBT Precursors : Sr[Ta(OEt)₅(OC₂H₄OMe)]₂/ ECH(0.05mol/L), Bi(MMP)₃/ ECH(0.1mol/L), PET/ ECH(0.05mol/L)

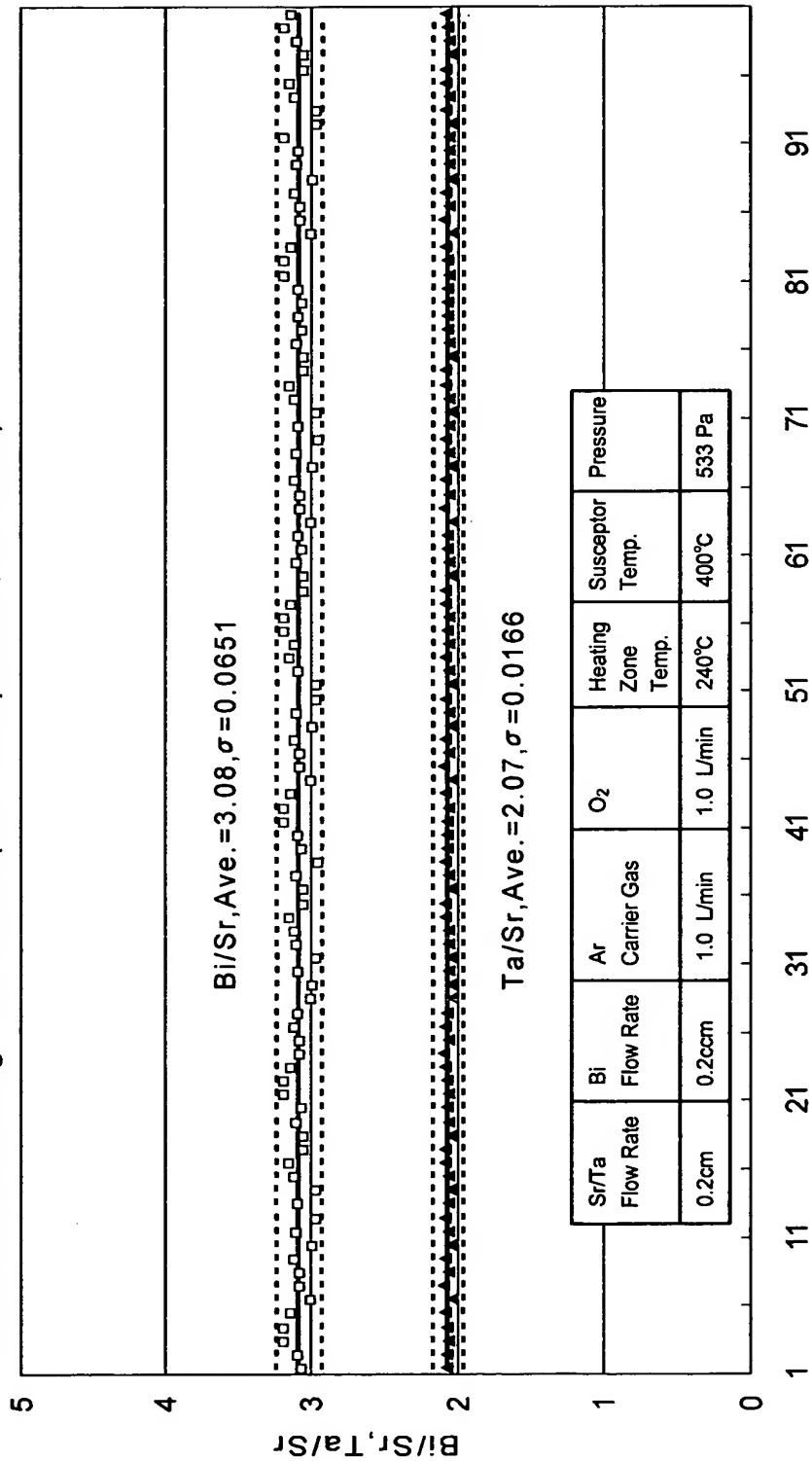
FIG.8



SBT Precursors : $\text{Sr}[\text{Ta}(\text{OEt})_3(\text{OC}_2\text{H}_4\text{OMe})]_2 / \text{ECH}(0.05\text{mol/L}), \text{Bi}(\text{MMP})_3 / \text{ECH}(0.1\text{mol/L}), \text{PET} / \text{ECH}(0.05\text{mol/L})$

FIG.9

Continuous Running Test Result (SBT Composition, Si Wafer)



No.

SBT Precursors : $\text{Sr}[\text{Ta}(\text{OEt})_5(\text{OC}_2\text{H}_4\text{OMe})]_2 / \text{ECH}(0.05\text{mol/L}), \text{Bi}(\text{MMP})_3 / \text{ECH}(0.1\text{mol/L}), \text{PET} / \text{ECH}(0.05\text{mol/L})$

FIG.10

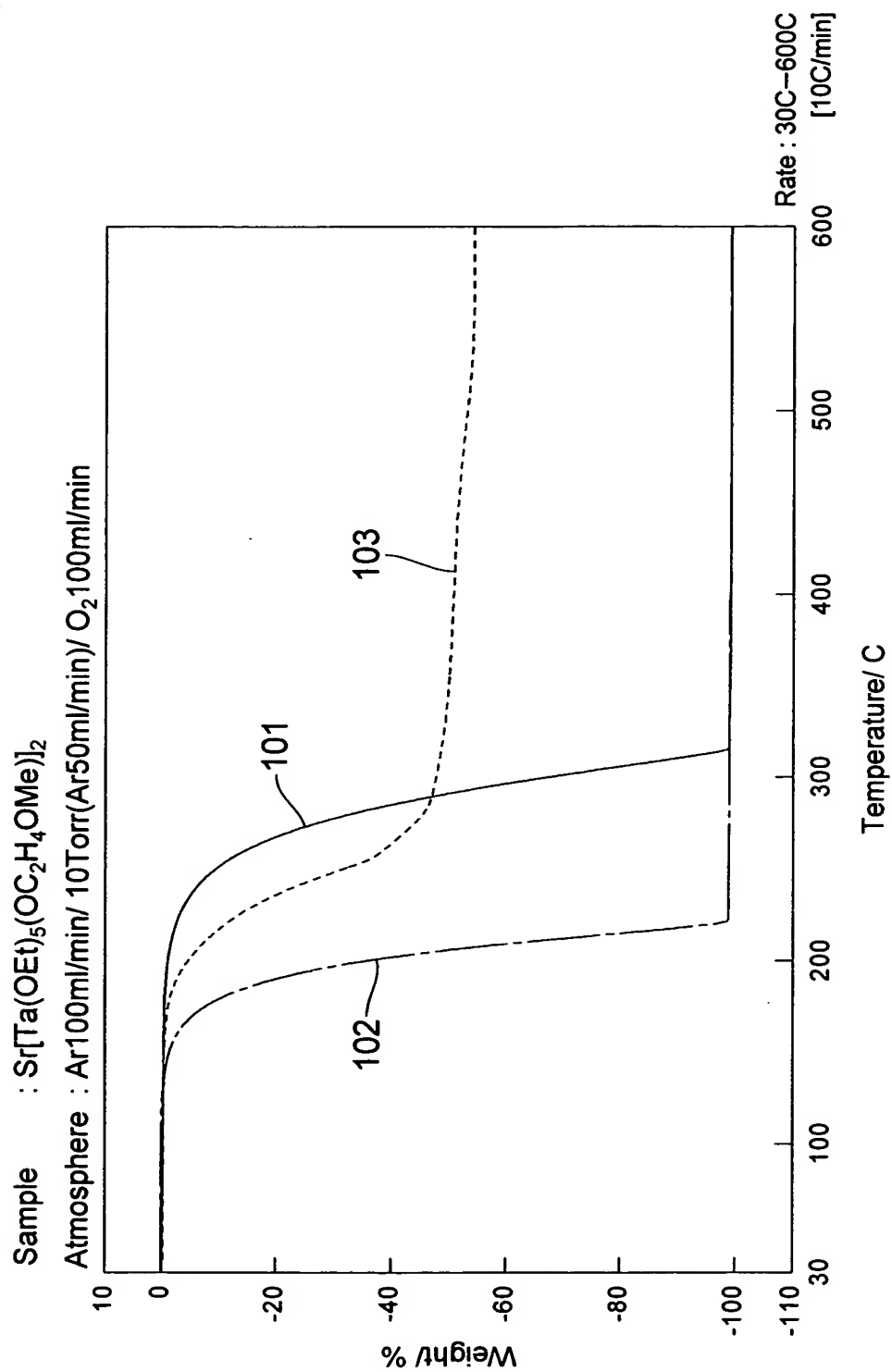


FIG.11

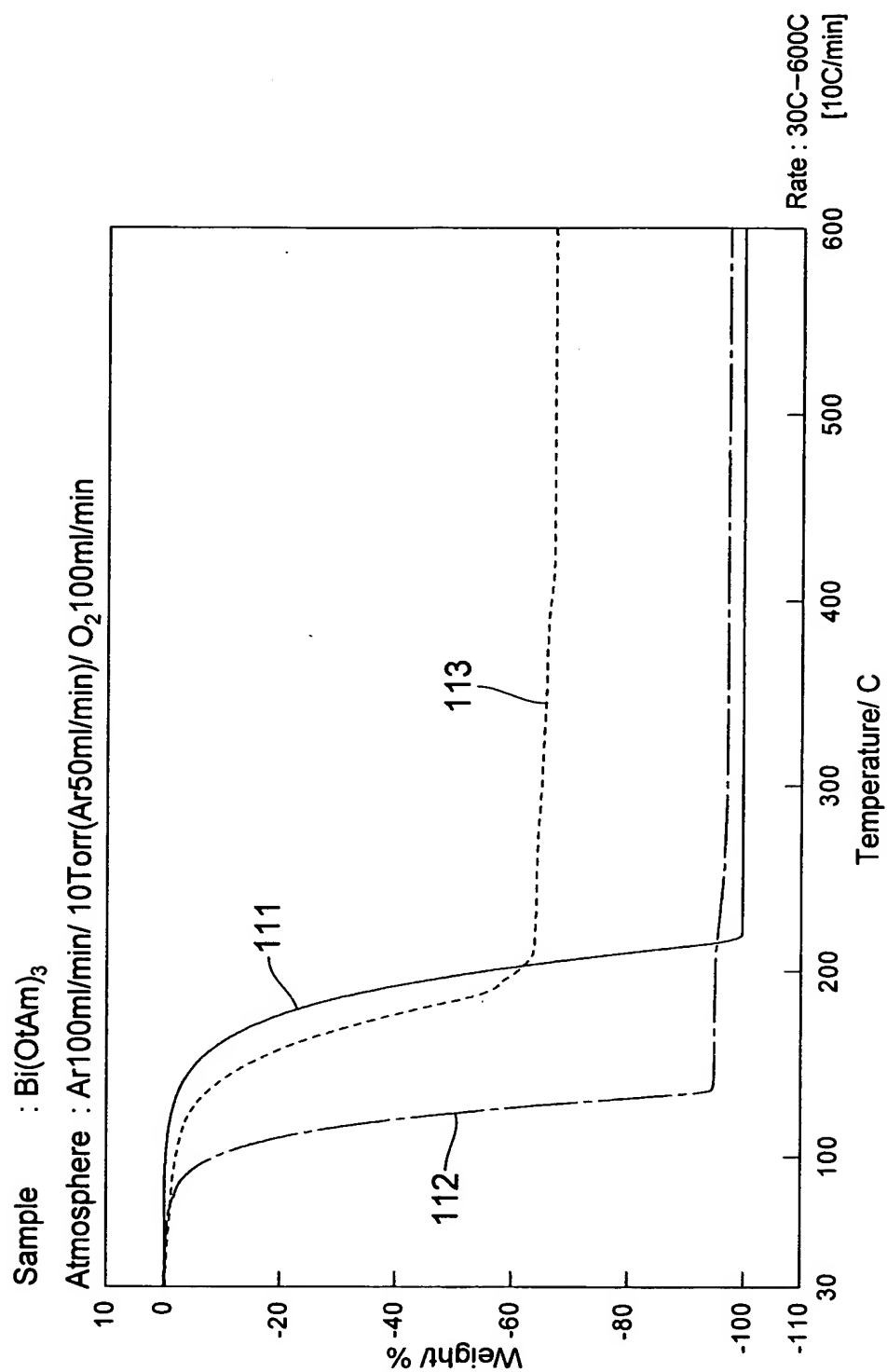


FIG.12

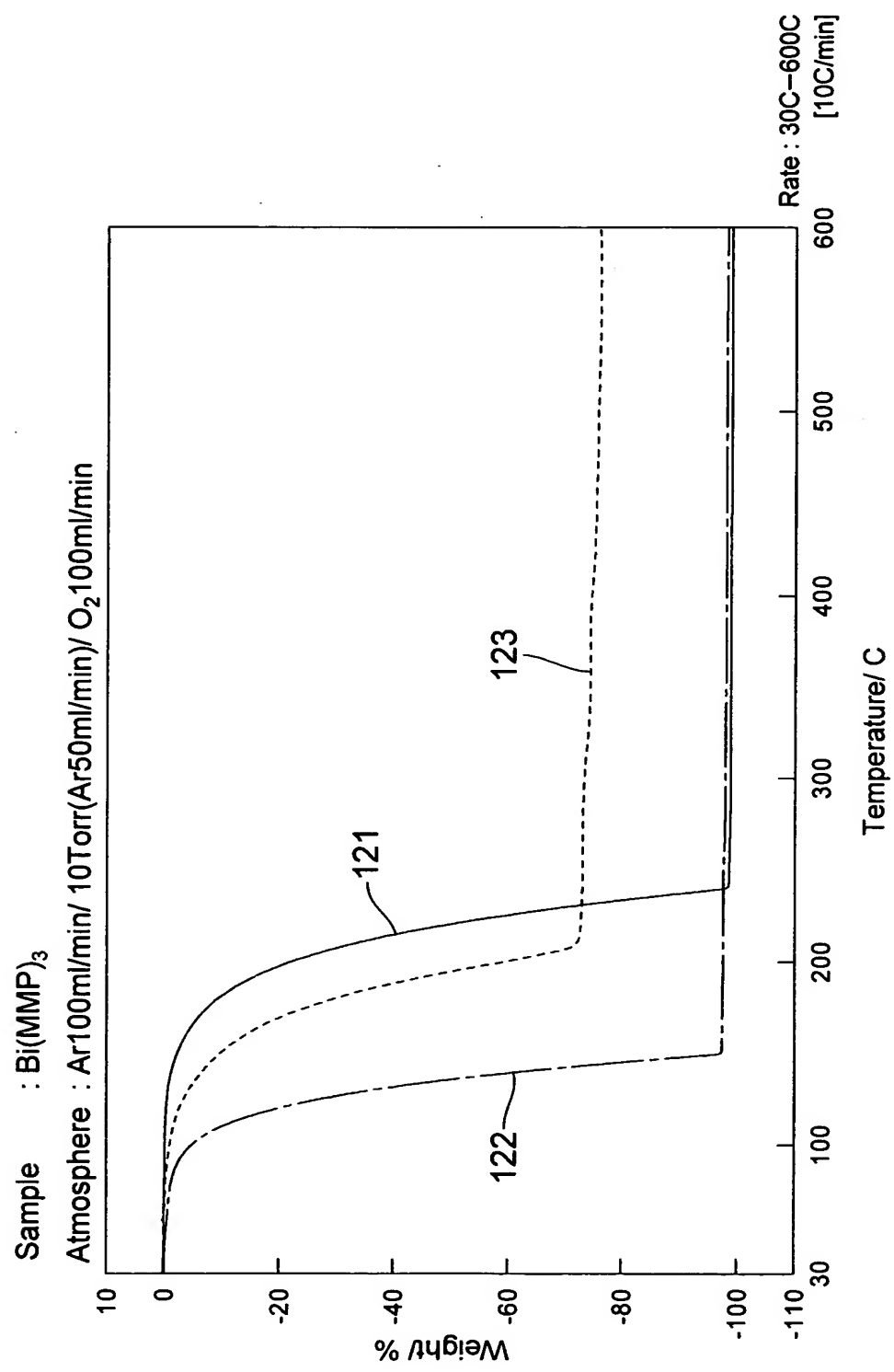


FIG.13

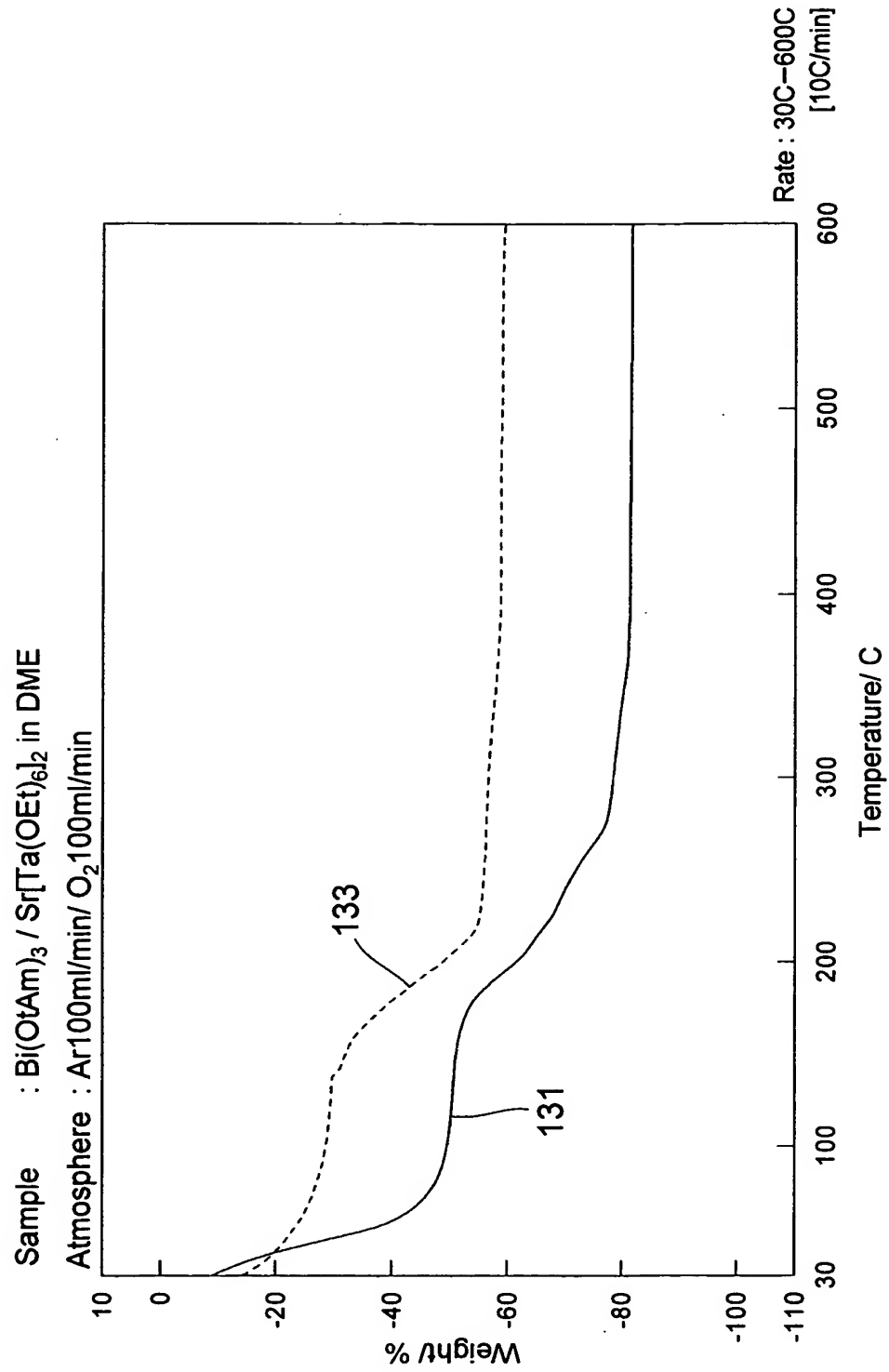


FIG.14

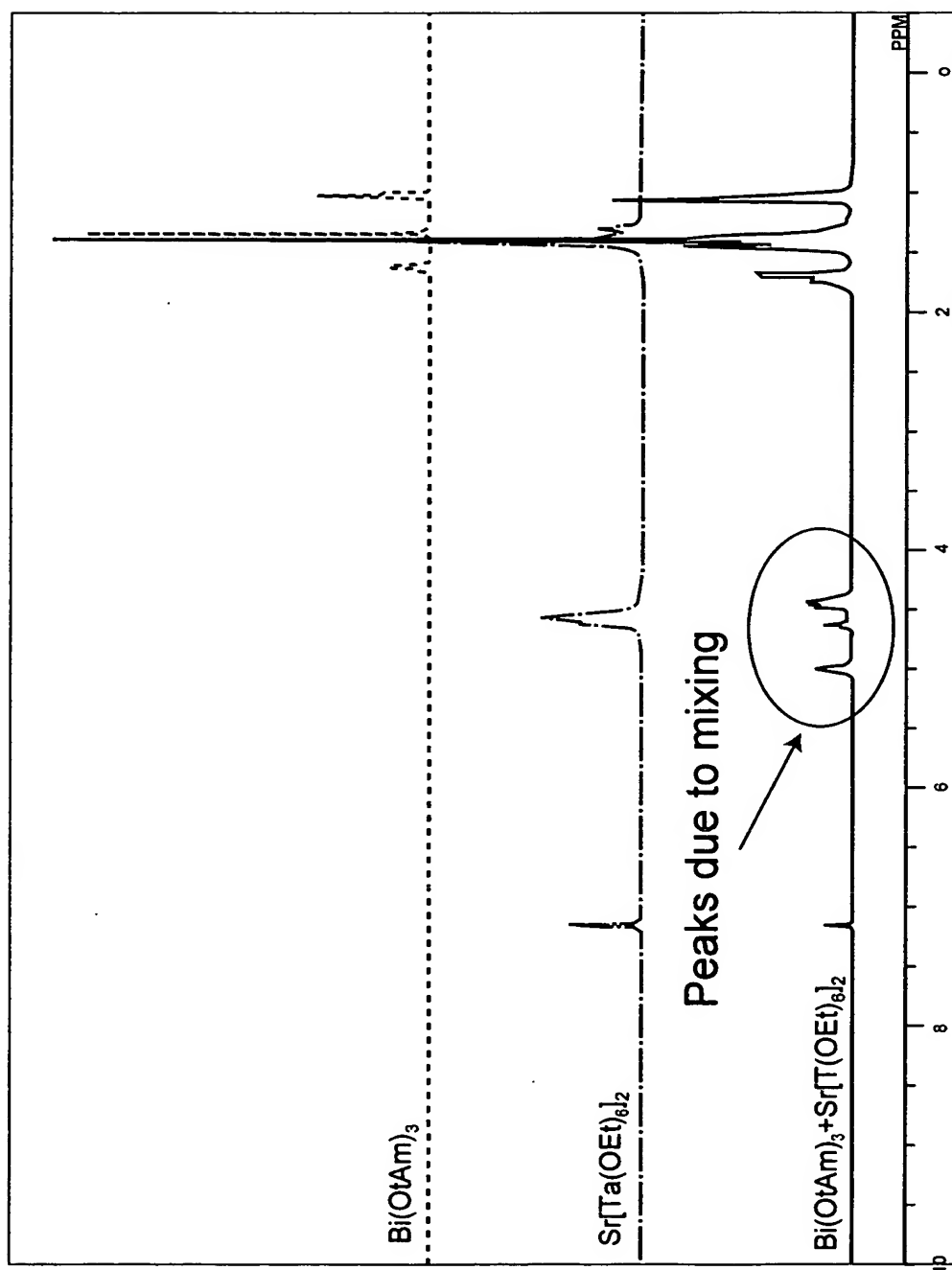


FIG.15

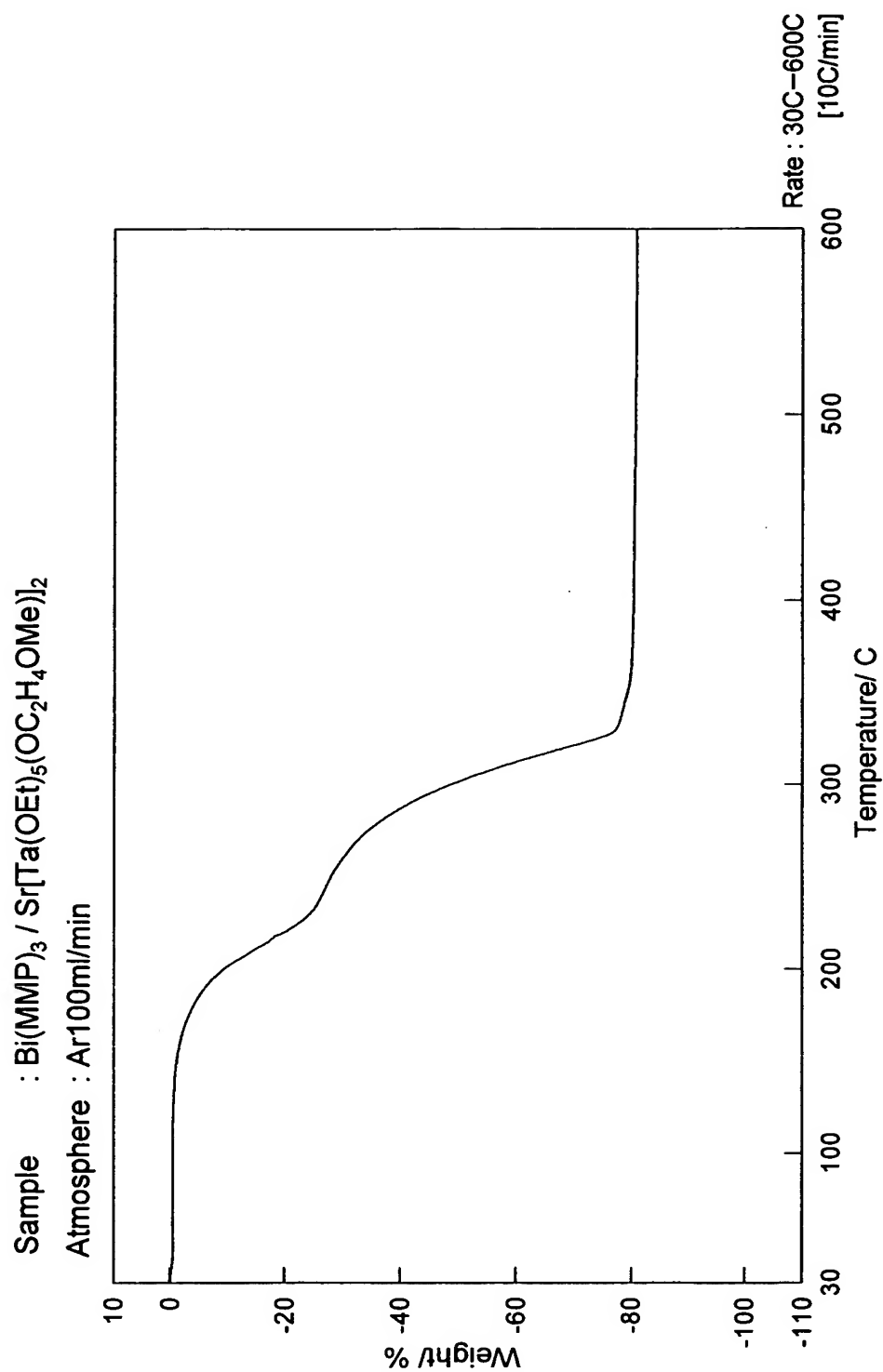


FIG.16

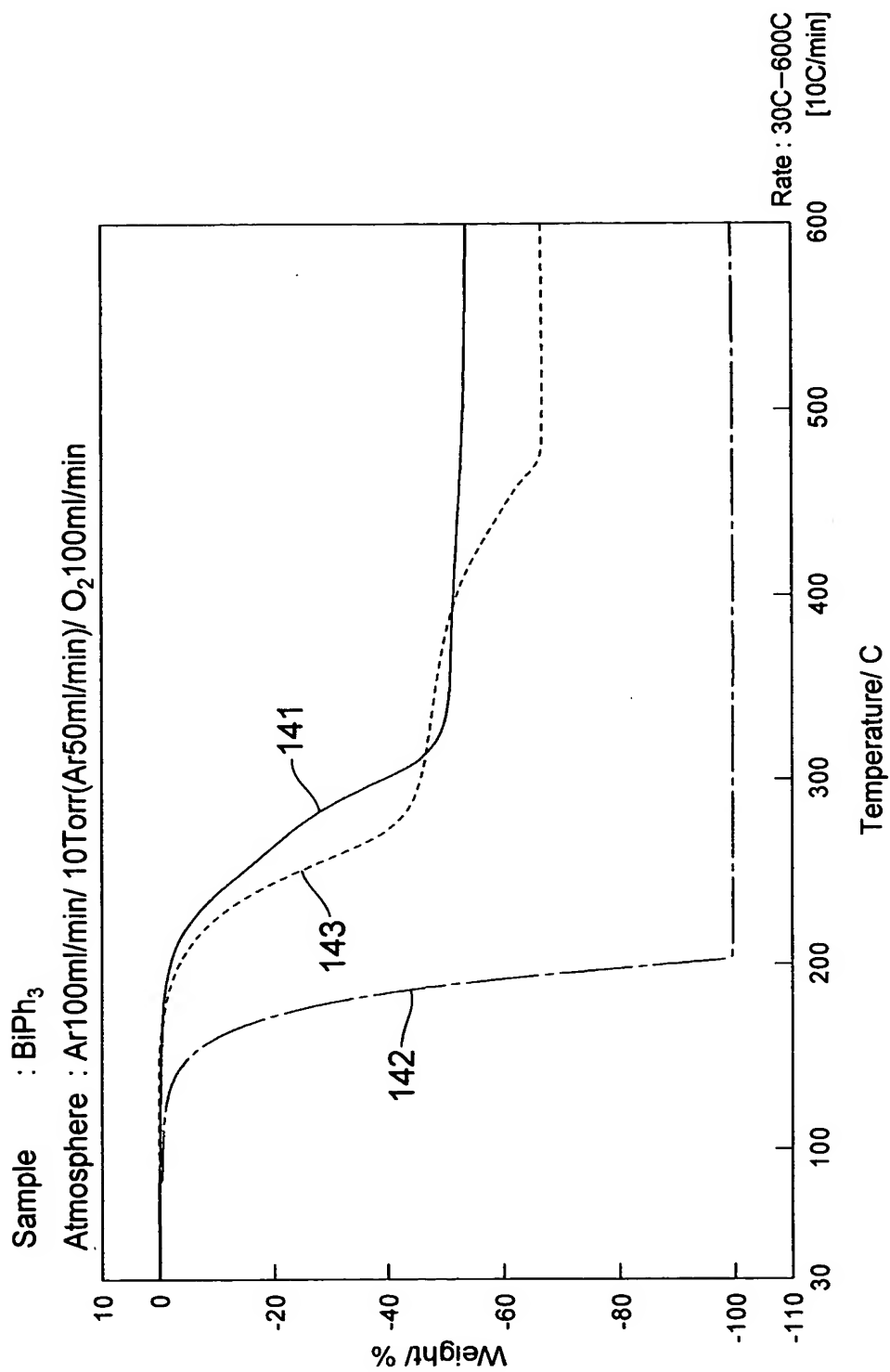


FIG.17

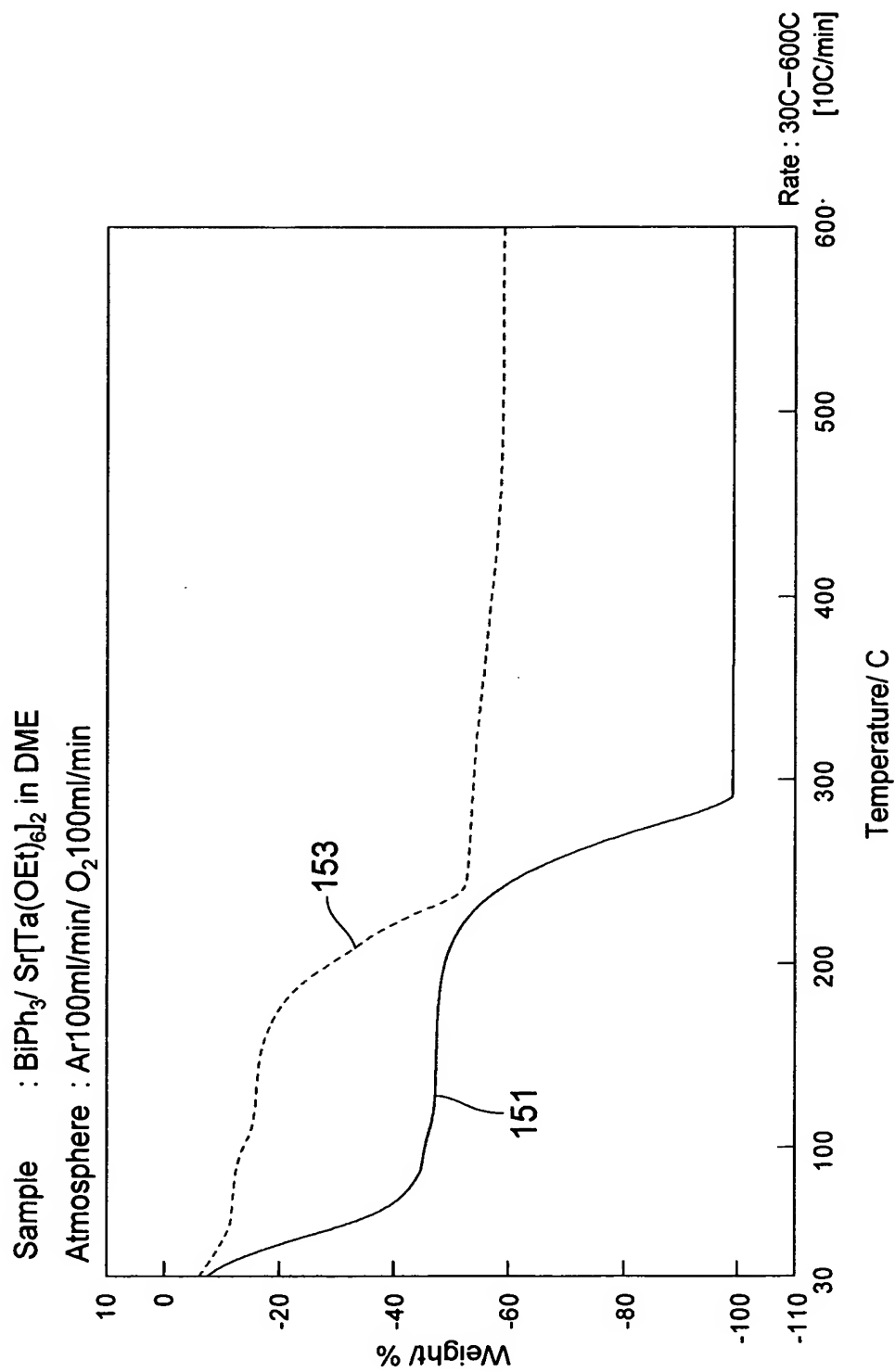


FIG.18

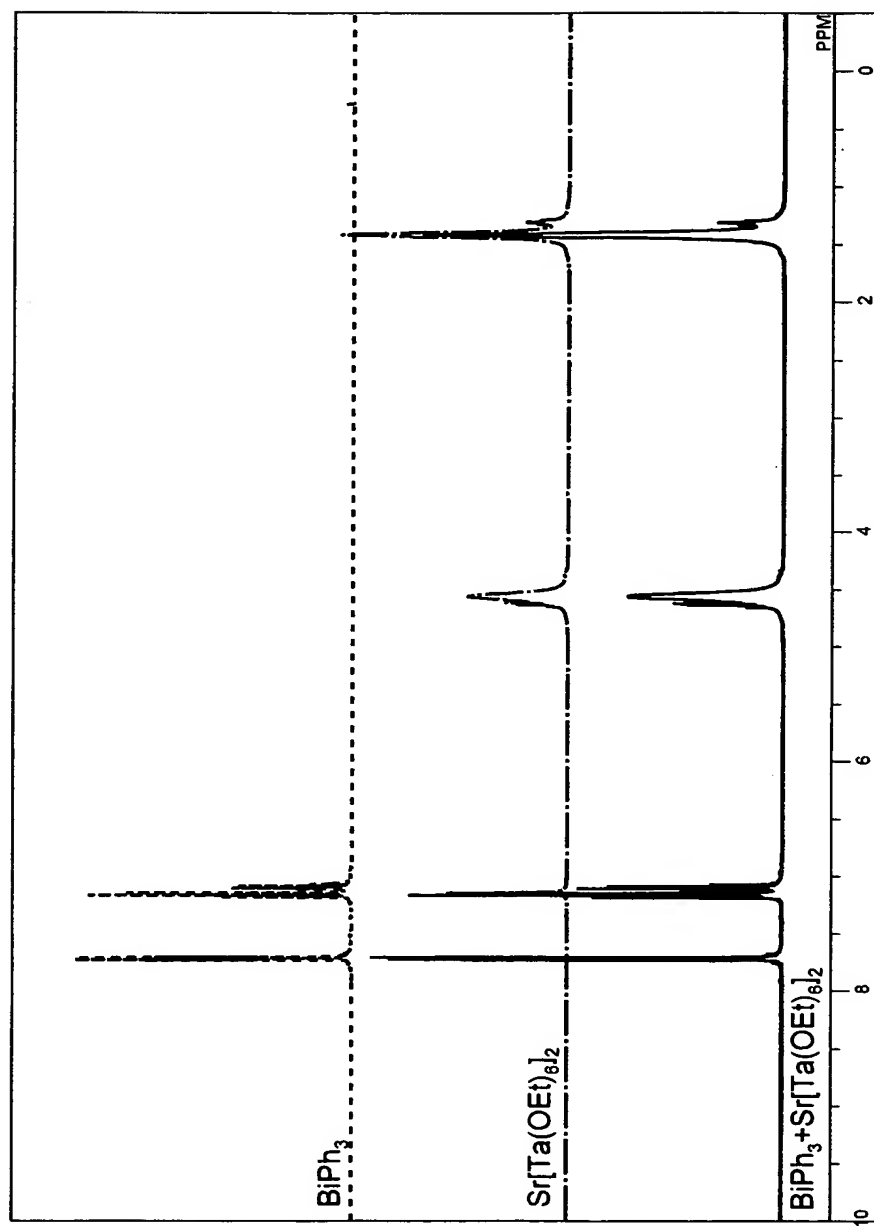


FIG.19

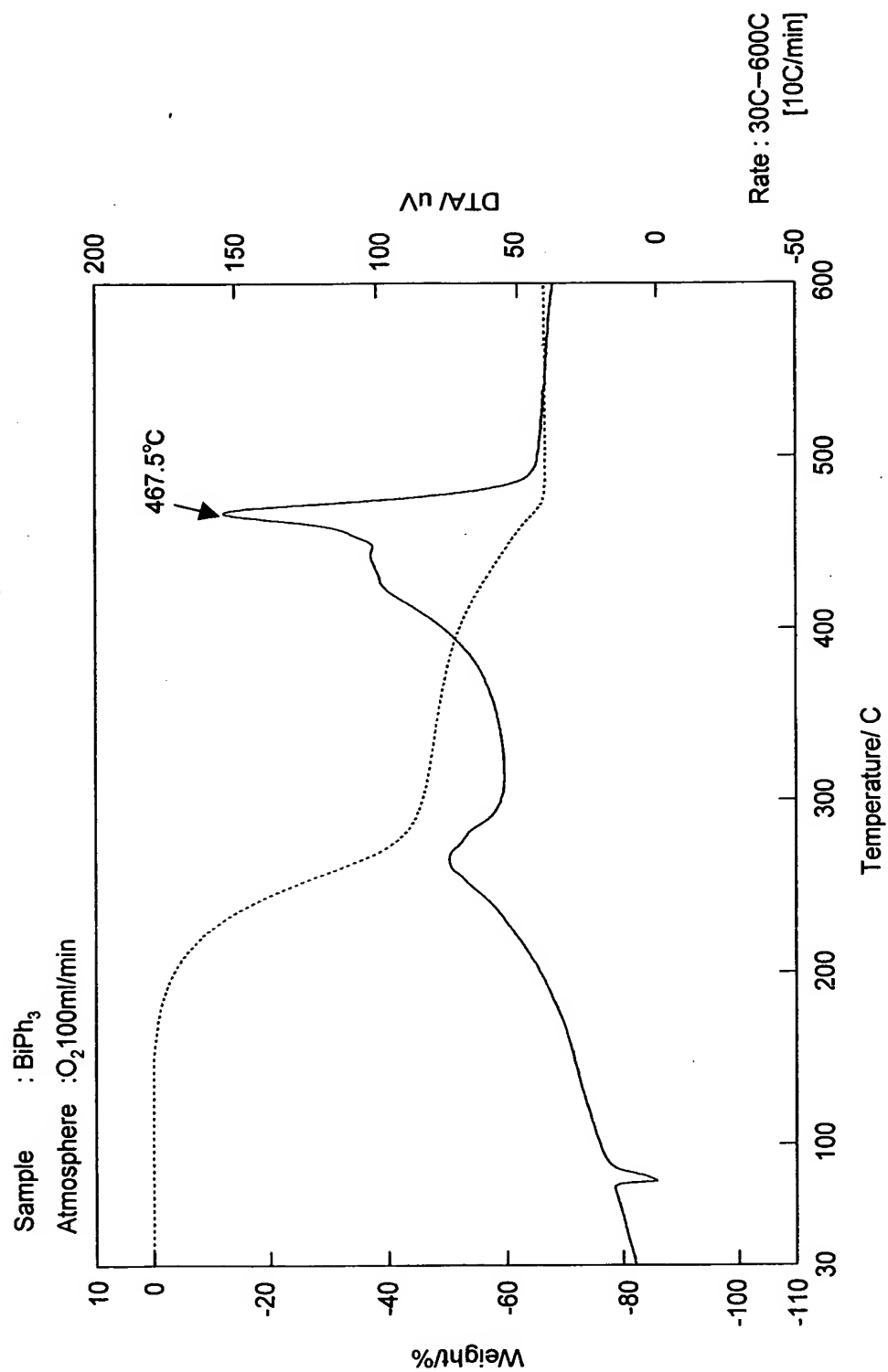


FIG.20